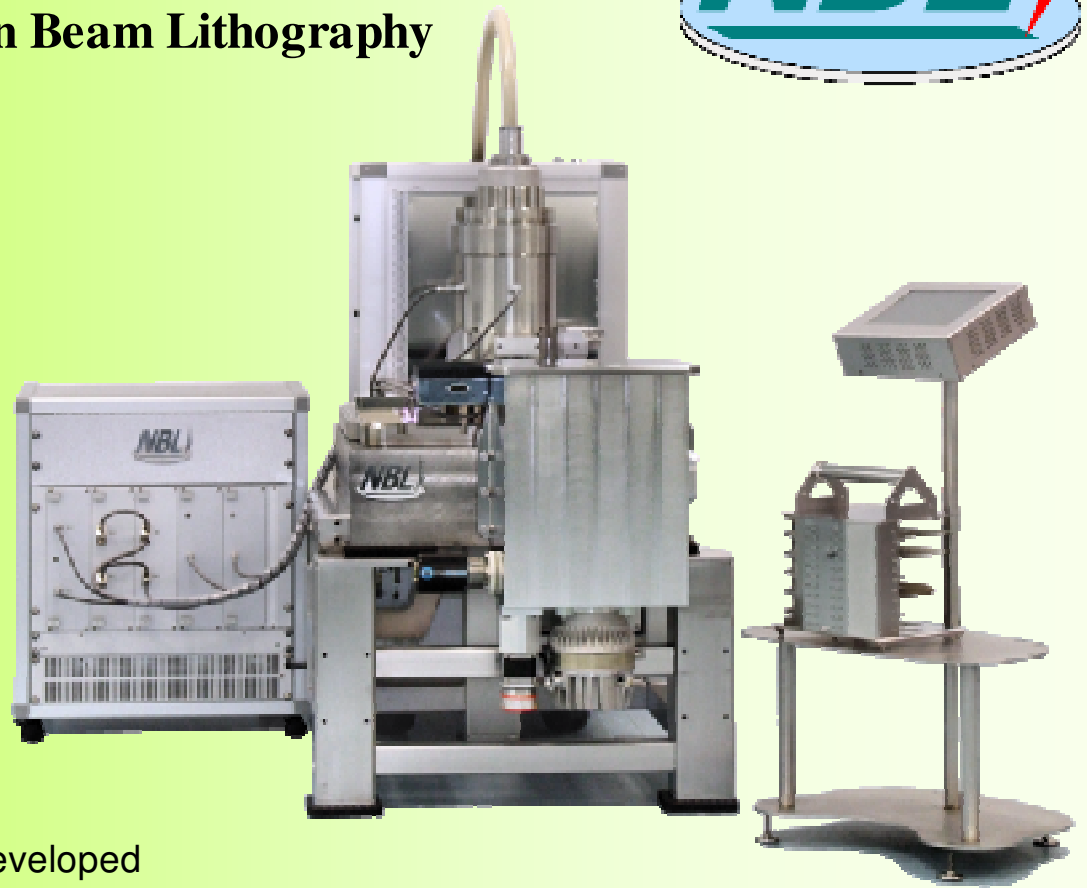


NanoBeam

Advanced Electron Beam Lithography

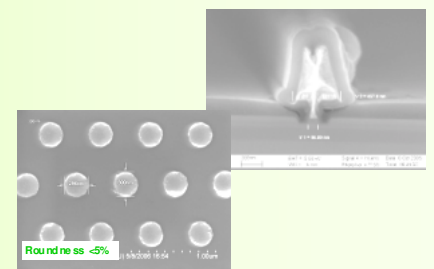


NanoBeam,

founded in 2002, has developed breakthrough technology to produce high performance and cost effective electron beam lithography tools.

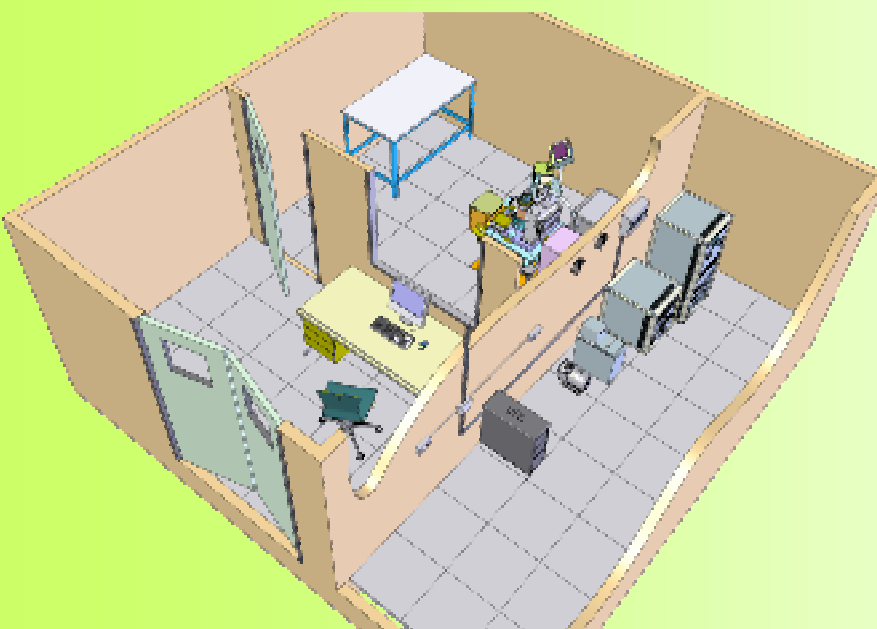
Our innovative designs significantly reduce product cost and therefore the ownership cost without compromising on accuracy or automation.

Small machine size, excellent resistance to stray field, advanced vibration tracking, and low power dissipation result in low cleanroom requirements.



Outstanding mechanical rigidity and fast stage and beam deflection settling result in higher throughput in mix-and-match and direct write.

The modern architecture requires fewer mechanical and electronic system components, which simplifies service and makes our products very reliable.





Inspiration into Performance

- Unique Electron Optical Column
 - Innovative Loading System
 - Designed for Reliability
 - High Resolution and Accuracy
 - 55MHz Deflection
 - 20bit DAC Resolution
 - Tracking down to 2kHz Vibration
 - Total Noise <3nm
 - Resistant to 600nT Stray Field
 - Install at Any Floor Level
 - Quick Installation
- Throughput *high*
 - Uptime *high*
 - Capital cost *low*
 - Operation cost *low*

A Tool for the Future

